

**RECEIVED  
CENTRAL FAX CENTER****APR - 6 2006****IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In Re Application of:	)	
	)	ATTORNEY FILE NO.:
Inventors: Joshi et al.	)	SLA0786
	)	
Serial No.: 10/812,591	)	
	)	Examiner: Sarkar, Asok
	)	
Filed: March 29, 2004	)	Customer No.: 55,286
	)	
Title: HIGH DENSITY PLASMA	)	Group Art: 2891
PROCESS FOR THE TRANS-	)	
FORMATION OF SILICON	)	Confirmation No.: 2314
DIOXIDE ON SILICON	)	
CARBIDE SUBSTRATES	)	

Mail Stop Amendments  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**CERTIFICATION UNDER 37 CFR § 1.8**

I hereby certify that this correspondence is being facsimile transmitted to the US Patent and Trademark Office, fax No. 571 278 8300, on this date 4/6/2006.

Date

4/6/2006

Signature

**RESPONSE UNDER 37 CFR 1.111**

In response to an Office Action mailed January 18, 2006,  
please amend and reconsider the above-referenced application as follows.

Amendments to the specification begin on page 2 of this  
paper.

Amendments to the claims begin at page 3 of this paper.

Remarks begin at page 16 of this paper.

Attached is the affidavit of Dr. Yoshi Ono.

Attached are a fee determination record and a PTO-2038  
credit card payment form.

04/07/2006 TL0111 00000005 10012591

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02 FC:12021000.00 OP  
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